Amendments to the Claims:

The following listing of claims will replace all prior versions, and listings, of claims in the application:

- (Currently Amended) A wiring substrate, comprising:
 a wiring layer formed on a substrate; and
 terminal electrodes that are coupled to the wiring layer and disposed on the
 substrate at locations of the substrate based on a stress distribution that works on the
 substrate.
- (Previously Presented) A wiring substrate, comprising:

 a wiring layer formed on a substrate; and
 terminal electrodes that are coupled to the wiring layer and disposed on the

 substrate in a manner to avoid diagonal lines thereof.
- 3. (Previously Presented) A wiring substrate, comprising:
 a wiring layer formed on a substrate;
 terminal electrodes that are coupled to the wiring layer and disposed on the
 substrate; and
 stress insulation sections provided along diagonal lines of the substrate.
- 4. (Previously Presented) The wiring substrate according to claim 3, the stress insulation sections being at least one of grooves and slits.
- 5. (Previously Presented) A wiring substrate, comprising:
 a wiring layer formed on a substrate;
 terminal electrodes that are coupled to the wiring layer and disposed on the substrate; and

dummy terminals that are provided in four corners or on diagonal lines of the substrate.

6. (Previously Presented) A semiconductor device, comprising:
 a semiconductor chip having an active region and pad electrodes formed
 thereon;

a stress buffer layer formed on the active region;

bump electrodes that are formed on the stress buffer layer and disposed based on a stress distribution that works on the semiconductor chip;

rearrangement wiring layers that couple the bump electrodes and the pad electrodes; and

a protection layer that is formed over the rearrangement wiring layers and the pad electrodes.

(Previously Presented) A semiconductor device, comprising:
 a semiconductor chip having an active region and pad electrodes formed
 thereon;

a stress buffer layer formed on the active region;

bump electrodes that are formed on the stress buffer layer and disposed in a manner to avoid diagonal lines thereof;

rearrangement wiring layers that couple the bump electrodes and the pad electrodes; and

a protection layer that is formed over the rearrangement wiring layers and the pad electrodes.

8. (Previously Presented) A semiconductor device, comprising:
 a semiconductor chip having an active region and pad electrodes formed
 thereon;

stress buffer layers that are formed on the active region, and divided and disposed along diagonal lines;

bump electrodes formed on the stress buffer layers;

rearrangement wiring layers that couple the bump electrodes and the pad electrodes; and

protection layers that are formed over the rearrangement wiring layers and the pad electrodes, and divided and disposed along the diagonal lines.

(Previously Presented) A semiconductor device, comprising:
 a semiconductor chip having an active region and pad electrodes formed
 thereon;

a stress buffer layer that is formed on the active region;

bump electrodes formed on the stress buffer layer;

dummy bumps provided in four corners or on diagonal lines of the stress buffer layer;

rearrangement wiring layers that couple the bump electrodes and the pad electrodes; and

a protection layer that is formed over the rearrangement wiring layers and the pad electrodes.

10. (Previously Presented) A semiconductor module, comprising:
 an interposer substrate having a semiconductor chip surface-mounted thereon;
 a wiring layer provided on a back surface of the interposer substrate;

bump electrodes that are coupled to the wiring layer and disposed based on a stress distribution that works on the interposer substrate; and

through hole wirings that are provided in the interposer substrate and couple the semiconductor chip and the wiring layer.

11. (Previously Presented) A semiconductor module, comprising:an interposer substrate having a semiconductor chip surface-mounted thereon;

a wiring layer provided on a back surface of the interposer substrate;

bump electrodes that are coupled to the wiring layer and disposed on the back surface of the interposer substrate in a manner to avoid diagonal lines; and

through hole wirings that are provided in the interposer substrate and couple the semiconductor chip and the wiring layer.

12. (Previously Presented) A semiconductor module, comprising:

an interposer substrate having a semiconductor chip surface-mounted thereon;

a wiring layer provided on a back surface of the interposer substrate;

bump electrodes that are coupled to the wiring layer and disposed on the back surface of the interposer substrate in a manner to avoid diagonal lines;

at least one of grooves and slits provided along diagonal lines of the interposer substrate; and

through hole wirings that are provided in the interposer substrate and couple the semiconductor chip and the wiring layer.

13. (Previously Presented) A semiconductor module, comprising:

an interposer substrate having a semiconductor chip surface-mounted thereon;

a wiring layer provided on a back surface of the interposer substrate;

bump electrodes that are coupled to the wiring layer and disposed on the back surface of the interposer substrate;

dummy bumps provided in four corners or on diagonal lines of the back surface of the interposer substrate; and

through hole wirings that are provided in the interposer substrate and couple the semiconductor chip and the wiring layer.

14. (Previously Presented) An electronic device, comprising:
an interposer substrate having a semiconductor chip surface-mounted thereon;

a wiring layer provided on a back surface of the interposer substrate;

bump electrodes that are coupled to the wiring layer and disposed on the back surface of the interposer substrate in a manner to avoid diagonal lines;

through hole wirings that are provided in the interposer substrate and couple the semiconductor chip and the wiring layer;

a mother substrate having the interposer substrate mounted thereon; and an electronic component that is coupled to the bump electrodes through the mother substrate.

15-22. (Canceled)